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## 13.5nm, 25.4mm Dia, 5° AOI, EUV Spherical Mirror



TECHSPEC® Extreme Ultraviolet (EUV) Spherical Mirrors

Stock #11-730 **20+ In Stock**

C\$6,034<sup>00</sup>

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### Volume Pricing

Qty 1+	C\$6,034.00 each
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### General

Spherical Mirror **Type:**

### Physical & Mechanical Properties

25.40 +0.00/-0.13 **Diameter (mm):**

6.35 ±0.25 **Thickness (mm):**

<3 RMS **Surface Roughness (□):**

## Optical Properties

Metal/Semiconductor	<b>Coating Type:</b>
Mb/Si Multilayer Top Layer: Silicon	<b>Coating:</b>
$\lambda/10$ @ 632.8nm	<b>Surface Flatness (P-V):</b>
13.5	<b>Design Wavelength DWL (nm):</b>
250.00	<b>Effective Focal Length EFL (mm):</b>
<b>Fused Silica</b> (Corning 7980)	<b>Substrate:</b> <input type="checkbox"/>
5	<b>Angle of Incidence (°):</b>
$R_{\text{abs}} > 60\%$ @ 13.5nm	<b>Coating Specification:</b>
500.00	<b>Radius <math>R_1</math> (mm):</b>
500.00	<b>Radius of Curvature (mm):</b>
0.50	<b>Full Width-Half Max FWHM (nm):</b>

## Regulatory Compliance

<a href="#">View</a>	<b>Certificate of Conformance:</b>
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## Product Details

- Mo/Si Multilayer Coating on Super-Polished Substrates
- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Focusing Applications
- Narrow Pass Band for HHG Applications

Extreme Ultraviolet (EUV) Spherical Mirrors feature a multilayer Mo/Si coating providing greater than 60% reflection at 13.5nm. They are designed for a 5° angle of incidence and intended for focusing unpolarized EUV laser sources. A surface roughness of less than 3Å RMS minimizes scatter. This is essential for EUV wavelengths which experience more scattering than longer wavelengths. EUV Spherical Mirrors have a very narrow pass band of approximately 0.5nm, ensuring that only the 13.5nm harmonic of interest is reflected in high harmonic generation (HHG) applications. [Typical applications](#) for EUV spherical mirrors include Coherent Diffractive Imaging (CDI), EUV imaging, and EUV nanomachining.

**Note:** Test data from each mirror's production run sample included.